

IN THE SPECIFICATION:

Please delete paragraph [0048] and replace with the following paragraph:

[0048] The beam PB subsequently intercepts the mask MA which is held in a mask holder on a mask table MT. Having traversed the mask MA, the beam PB passes through the lens PL, which focuses the beam PB onto a target portion C of the substrate W. With the aid of the interferometric displacement measuring means IFa and IFb, the substrate tables WT_a, WT_b can be moved accurately by the second and third positioning means, e.g. so as to position different target portions C in the path of the beam PB. Similarly, the first positioning means can be used to accurately position the mask MA with respect to the path of the beam PB, e.g. after mechanical retrieval of the mask MA from a mask library or during a mask scan. In general, movement of the tables MT, WT_a, WT_b will be realised with the aid of a long-stroke module ([course] coarse positioning) and a short-stroke module (fine positioning), which are not explicitly depicted in Figure 1. In the case of a wafer stepper (as opposed to a step-and-scan apparatus) the mask table MT may be connected only to a short stroke-positioning device, to make fine adjustments in mask orientation and position, or the mask table MT may be just fixed. The second and third positioning means may be constructed so as to be able to position the substrate tables WT_a, WT_b over a range encompassing both the first station Sa under projection system PL and the second station Sb under the levelling system LS. Suitable positioning systems are described, inter alia, in WO 98/28665 and WO 98/40791 mentioned above. It should be noted that a lithography apparatus may have multiple exposure stations and/or multiple metrology stations and that the numbers of metrology and exposure stations may be different than each other and the total number of stations need not equal the number of substrate tables. Indeed, the principle of separate exposure and metrology stations may be employed with one or more substrate tables.